

Page 13, delete the whole paragraph starting in line 6 and replace it with the following new paragraph:

b2 [0083] In a further variant, the spot (or object such as a mask defining a spot) can be displaced from the object focal plane at the entrance to the projection lens. For example, a quartz reticle, with a chromium pattern on one surface defining a pinhole, can be turned upside-down so that the pinhole is displaced from the focal plane along the optical axis by a distance equal to the thickness of the reticle. In this way, there is no longer a focused image of the spot at the wafer level, so the sensor 16 can, in fact, be located at the plane corresponding to wafer level, i.e. the focal plane of the projection lens. In this variant, the sensor will be defocused with respect to a spot or image of a spot, even though the sensor is at the focal plane of the projection lens. This defocus of the sensor is a requirement common to different embodiments of the present invention.

*See the attached Appendix for the changes made to effect the above paragraph.*

IN THE CLAIMS:

Please enter the following amended claims.

- b3 12. (Amended) An apparatus according to claim 11, wherein said at least one spot formation device comprises at least one pinhole located at one of the mask plane and the substrate plane.
13. (Amended) An apparatus according to claim 12, wherein the at least one pinhole further comprises subsidiary dots, of size substantially equal to a wavelength of the radiation.
14. (Amended) An apparatus according to claim 12, wherein the at least one pinhole further comprises a diffraction grating.
15. (Amended) An apparatus according to claim 12, wherein the at least one pinhole further comprises an element to provide an angular distribution of radiation using at least one